a second plate disposed adjacent to said first plate, wherein said second plate defines a second internal cavity configured to receive a second gas through a first passage into said second internal cavity at a first temperature and to emit said gas from said second internal cavity at a second temperature through a second passage.

- 3. (Allowed) The system of Claim 2, wherein said second passage comprise a plurality of holes defined on a surface of said first and said second plates.
- 4. (Allowed) The system of Claim 2, wherein said first plate and said second plate comprise a heat source for heating said plate to a preselected temperature.
- 5. (Allowed) The system of Claim 2, wherein said first gas is taken from the group consisting of N<sub>2</sub>, He, H<sub>2</sub>, O<sub>2</sub>, Ar and gas mixtures containing He, H<sub>2</sub>, O<sub>2</sub>, Ar and N<sub>2</sub>.
- 6. (Allowed) The system of Claim 2, wherein said internal cavity further comprises a buffer to disperse said first gas throughout said internal cavity.

Please cancel Claim 7.

- 8. (Allowed) A system for wafer processing comprising: a chamber, and at least one heatable plate positionable within said chamber, including: an internal cavity defining an internal wall and configured to receive a gas; means for heating said internal wall to a preselected temperature; and an outlet portion defining a plurality of holes for emitting said gas; said at least one heatable plate including a first heatable plate and a second heatable plate disposed having adjacent surfaces configured to receive a wafer therebetween.
- 9. (Allowed) The system of Claim 8, wherein said gas is taken from the group consisting of He, H<sub>2</sub>, O<sub>2</sub>, Ar, N<sub>2</sub> and gas mixtures containing He, H<sub>2</sub>, O<sub>2</sub>, Ar, and N<sub>2</sub>.

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